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(54) **RESIST COMPOSITION, METHOD OF FORMING RESIST PATTERN, COMPOUND, AND POLYMERIC COMPOUND**

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(58) **Field of Classification Search**

CPC G03F 7/004; G03F 7/039; G03F 7/0392; G03F 7/0397; C07C 69/604; C07C 69/74; C08F 222/10

See application file for complete search history.

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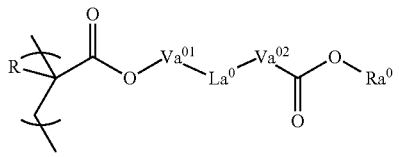
(57) **ABSTRACT**

A polymeric compound having a structural unit represented by general formula (a0-1), and a resist composition containing the same (in which R represents a hydrogen atom, an alkyl group of 1 to 5 carbon atoms or a halogenated alkyl group of 1 to 5 carbon atoms; Va^{01} and Va^{02} each independently represents a hydrocarbon group of 2 to 10 carbon atoms; Va^{01}-La^{0}— represents Va^{01}-C(=O)O— or Va^{01}-OC(=O)—; Ra^{0} represents an acid dissociable, branched hydrocarbon group of 8 or more carbon atoms, an acid dissociable, monocyclic hydrocarbon group of 4 or more carbon atoms, or an acid dissociable, polycyclic hydrocarbon group, provided that methyl adamantyl group is excluded.

(a0-1)



17 Claims, No Drawings